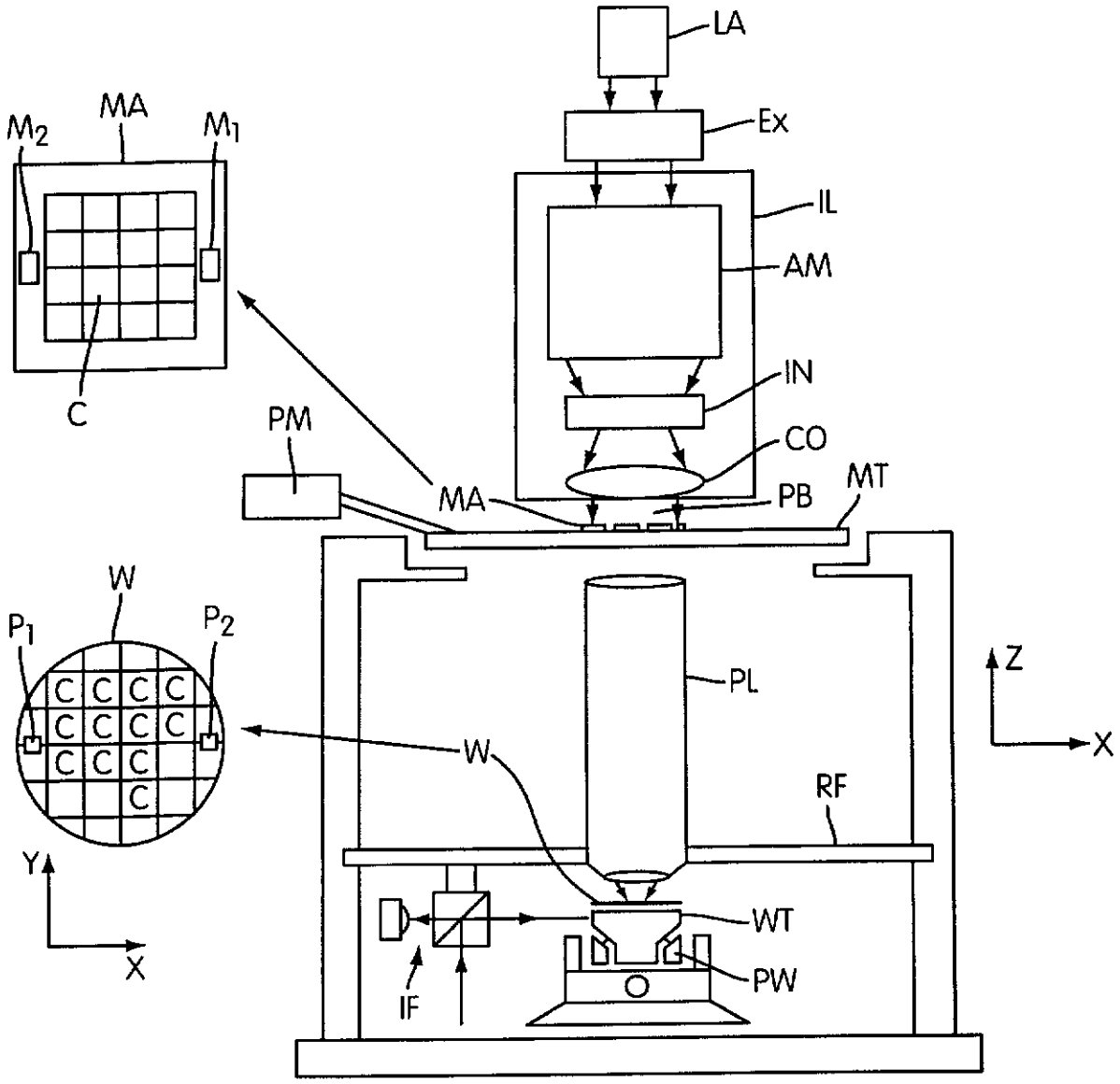

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FIG. 1

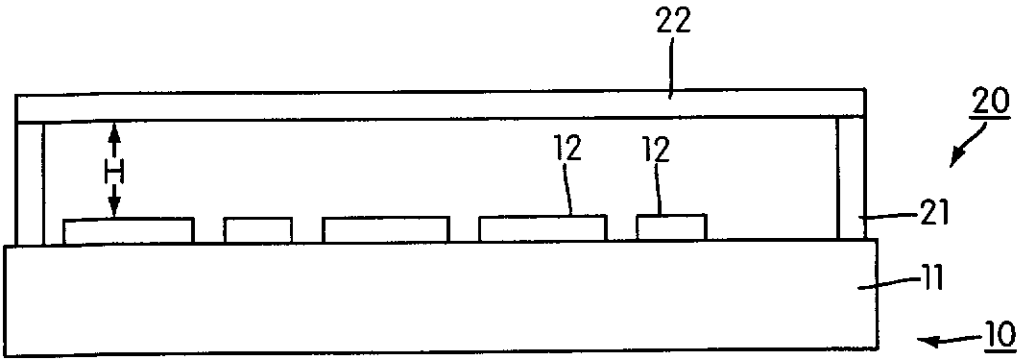


FIG. 2
PRIOR ART

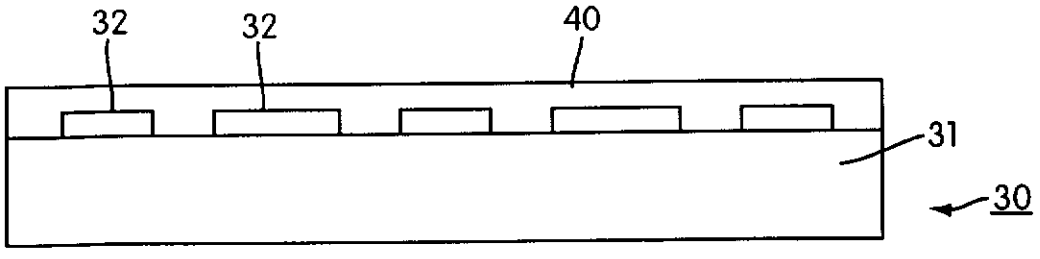


FIG. 3

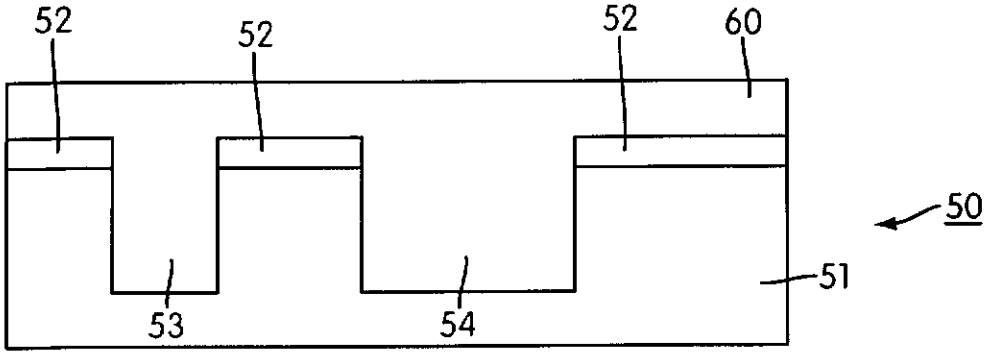


FIG. 4

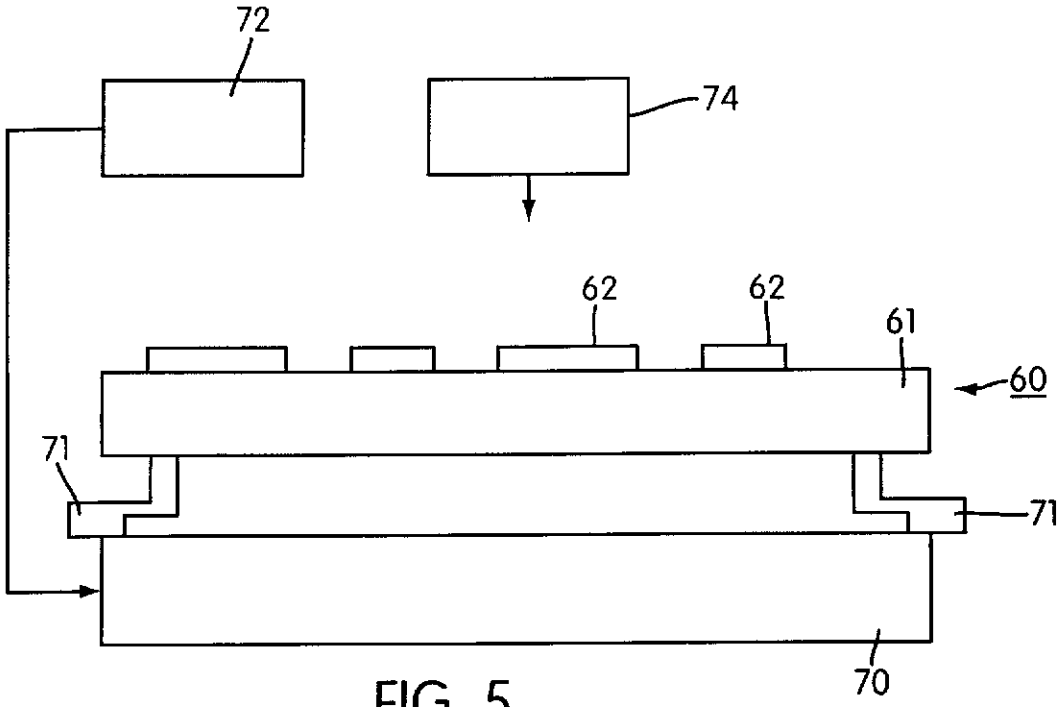


FIG. 5

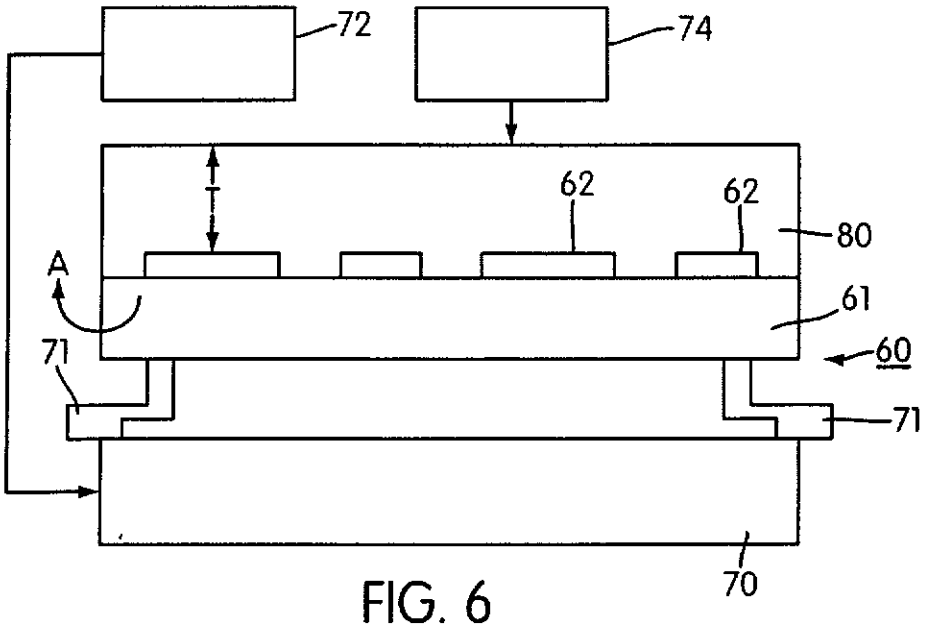


FIG. 6

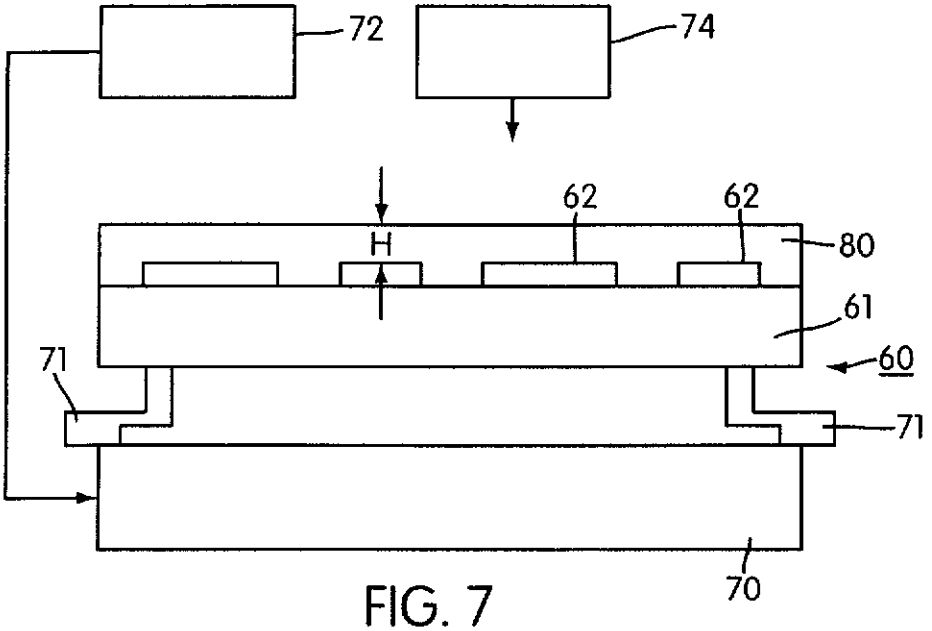


FIG. 7

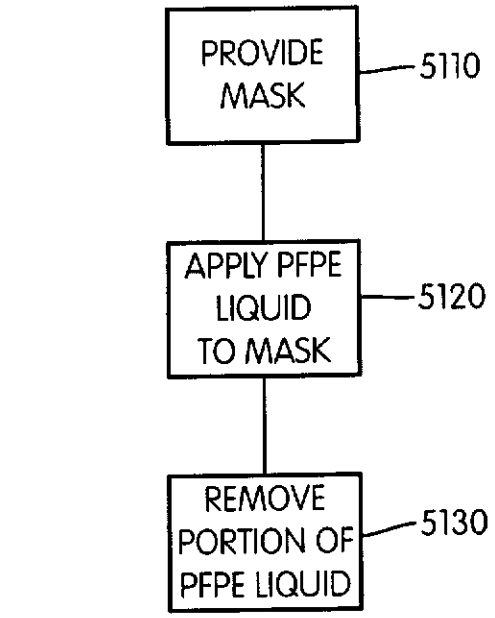

PROVIDE MASK
5110
APPLY PFPE LIQUID TO MASK
5120
REMOVE PORTION OF PFPE LIQUID
5130

FIG. 8

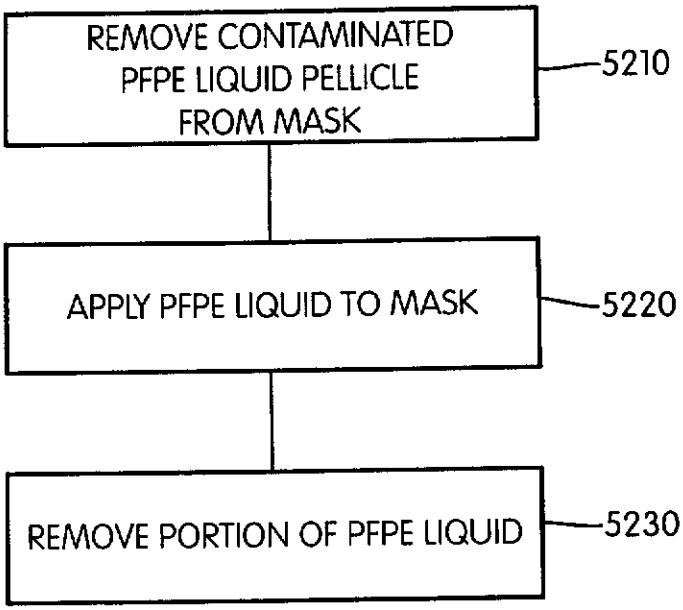

REMOVE CONTAMINATED PFPE LIQUID PELLICLE FROM MASK
5210
APPLY PFPE LIQUID TO MASK
5220
REMOVE PORTION OF PFPE LIQUID
5230

FIG. 9

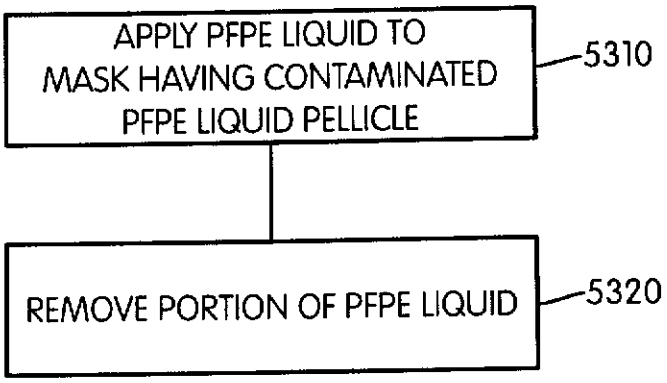

APPLY PFPE LIQUID TO MASK HAVING CONTAMINATED PFPE LIQUID PELLICLE
5310
REMOVE PORTION OF PFPE LIQUID
5320

FIG. 10

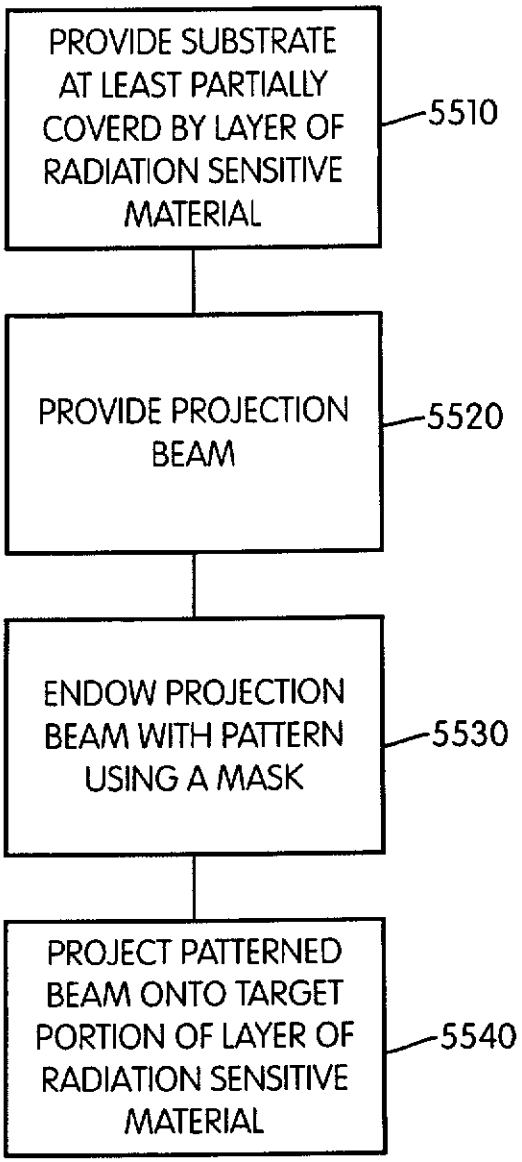

PROVIDE SUBSTRATE AT LEAST PARTIALLY COVERD BY LAYER OF RADIATION SENSITIVE MATERIAL
5510
PROVIDE PROJECTION BEAM
5520
ENDOW PROJECTION BEAM WITH PATTERN USING A MASK
5530
PROJECT PATTERNED BEAM ONTO TARGET PORTION OF LAYER OF RADIATION SENSITIVE MATERIAL
5540

FIG. 11

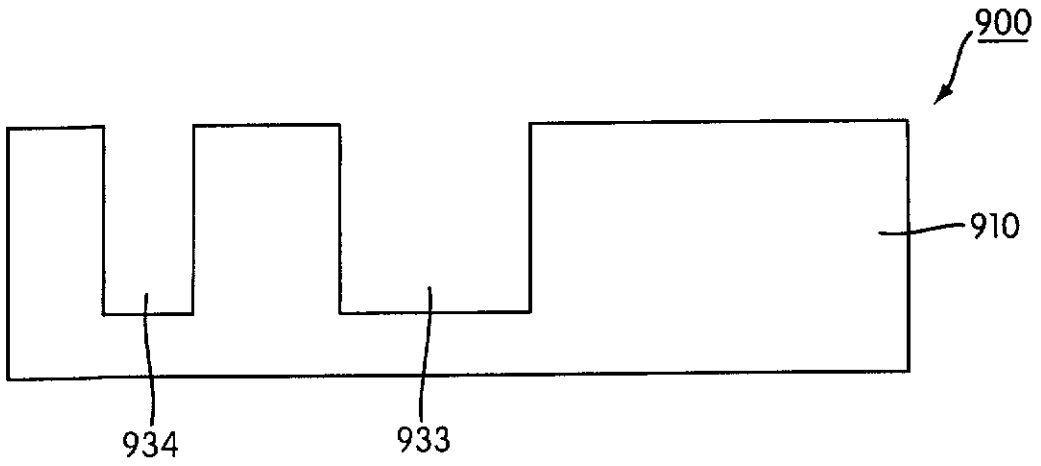


FIG. 12